IN THE CLAIMS:

Claims 1-24 Cancelled

Please enter the following new claims:

25. A method of making a fluoride crystalline optical lithography lens element blank, said method including:

forming a fluoride crystalline melt,

crystallizing said melt into a fluoride crystalline member with a large dimension ≥ 200 mm,

annealing said fluoride crystalline member, and

qualifying the resulting member for use as an optical lithography lens element by a method selected from the group consisting of:

- (a) measuring the absorption spectrum of the member from 200-220 nm for a 205 nm lead adsorption peak, and
 - (b) detecting radiation diffracted by the crystalline member.
- 26. The method according to claim 25, wherein measuring an absorption spectrum of the member from 200 to 220 nm for a 205 nm lead absorption peak further includes exciting the member with a 203 nm excitation radiation and measuring a luminescence spectrum produced by exciting the member to provide a qualified fluoride crystalline optical lithography lens element blank with a 157 nm internal absorption coefficient less than .0022/cm and a 193 nm internal absorption coefficient less than .00043/cm, a 205 nm lead absorption < .23 cm⁻¹ local extinction, a 306 nm cerium absorption < .7x10⁻³ cm⁻¹ local extinction, an average birefringence less than 2 nm/cm with a maximum birefringence less than 5 nm/cm, and an optical homogeneity less than 2 ppm with a surface subgrain disorientation boundary angle \leq 2 minutes.
- 27. The method as claimed in claim 26 wherein measuring includes analyzing said fluoride crystalline member for an oxygen absorption peak within the wavelength range of 140 to 150 nm.

- 28. The method as claimed in claim 26 wherein forming a fluoride crystalline melt includes melting a high purity calcium fluoride raw material having by weight impurity levels of \leq 1 ppm Li, \leq 3.3 ppm Na, \leq 3.8 ppm K, \leq .5 ppm Mg, \leq 19 ppm Sr, \leq .5 ppm Ba, < .2 ppm Sc, < .2 ppm Y, < .2 ppm La, \leq .2 ppm Gd, < .2 ppm Yb, < .2 ppm Ti, < .2 ppm Cr, \leq 4.2 ppm Mn, \leq .4 ppm Fe, \leq .2 ppm Co, < .2 ppm Ni, \leq .3 ppm Cu, < 200 ppm O.
- 29. The method as claimed in claim 26 wherein forming a fluoride crystalline melt includes providing at least one deoxygenated densified solid fluoride crystalline disk having a diameter ≥ 200 mm and melting the at least one deoxygenated densified solid fluoride crystalline ≥200 mm diameter disk.
- 30. The method as claimed in claim 26 wherein measuring said fluoride crystalline member includes exposing said fluoride crystalline member to a radiation source and detecting radiation diffracted by the fluoride crystalline member.
- 31. The method according to claim 25, wherein detecting radiation diffracted by the crystalline member includes

exposing said fluoride crystalline member to a radiation source and detecting radiation diffracted by the fluoride crystalline member to provide a qualified fluoride crystalline optical lithography lens element blank with a 157 nm internal absorption coefficient less than .0022/cm and a 193 nm internal absorption coefficient less than .00043/cm, a 205 nm lead absorption < .23 cm⁻¹ local extinction, a 306 nm cerium absorption < .7x10⁻³ cm⁻¹ local extinction, an average birefringence less than 2 nm/cm with a maximum birefringence less than 5 nm/cm, and an optical homogeneity less than 2 ppm with a surface subgrain disorientation boundary angle \leq 2 minutes.

- 32. The method as claimed in claim 31 including analyzing said fluoride crystalline member for an oxygen absorption peak within the wavelength range of 140 to 150 nm.
- 33. The method as claimed in claim 31 wherein forming a fluoride crystalline melt includes melting a high purity calcium fluoride raw material having by weight impurity levels

of \leq 1 ppm Li, \leq 3.3 ppm Na, \leq 3.8 ppm K, \leq .5 ppm Mg, \leq 19 ppm Sr, \leq .5 ppm Ba, < .2 ppm Sc, < .2 ppm Y, < .2 ppm La, \leq .2 ppm Gd, < .2 ppm Yb, < .2 ppm Ti, < .2 ppm Cr, \leq 4.2 ppm Mn, \leq .4 ppm Fe, \leq .2 ppm Co, < .2 ppm Ni, \leq .3 ppm Cu, < 200 ppm O.

- 34. The method as claimed in claim 31 wherein forming a fluoride crystalline melt includes providing at least one deoxygenated densified solid fluoride crystalline disk having a diameter ≥ 200 mm and melting the at least one deoxygenated densified solid fluoride crystalline ≥ 200 mm diameter disk.
- 35. The method as claimed in claim 31 including measuring an absorption spectrum of the member from 200 to 220 nm for a 205 nm lead absorption peak and exciting the member with a 203 nm excitation radiation and measuring a luminescence spectrum produced by exciting the member.